

In the Claims:

1. **(currently amended)** A process for the production of a strongly adherent coating on an inorganic or organic metalized substrate,
 - a) a low-temperature plasma treatment, a corona discharge treatment or a flame treatment is carried out on the inorganic or organic metalized substrate, wherein the substrate is metalized with layers of metal,
 - b) one or more photoinitiators or mixtures of photoinitiators with monomers or/and oligomers, containing at least one ethylenically unsaturated group, or solutions, suspensions or emulsions of the afore-mentioned substances, are applied to the inorganic or organic metalized substrate to form a layer which layer is optionally dried to remove solvent if present, and then
 - c) irradiating the layer of step b) with from 1 to 1000 mJ/cm² of UV/Vis light having wavelengths from 150 to 700 nm to fix the one or more photoinitiators in the layer of step b,
and either
 - d1) the substrate so precoated with photoinitiator is coated with a composition comprising at least one ethylenically unsaturated monomer or oligomer, and the coating is cured by means of UV/VIS radiation or an electron beam; or
 - d2) the substrate so precoated with photoinitiator is coated with a printing ink and dried.

2. **(cancelled)**

3. **(original)** A process according to claim 1, wherein the photoinitiator is a compound or combination of compounds from the classes of benzoins, benzil ketals, acetophenones, hydroxylalkylphenones, aminoalkylphenones, acylphosphine oxides, acylphosphine sulfides, acyloxyiminoketones, peroxy compounds, halogenated acetophenones, phenylglyoxylates, dimeric phenylglyoxalates, benzophenones, oximes and oxime esters, thioxanthones, thiazolines, ferrocenes, coumarins, dinitrile compounds, titanocenes, sulfonium salts, iodonium salts, diazonium salts, onium salts, borates, triazines, bisimidazoles, polysilanes and dyes, and also corresponding coinitiators and/or sensitizers.

4. **(original)** A process according to claim 1, wherein the photoinitiator is a compound of formula I or Ia

(RG)-A-(IN) (I),

(IN)-A-(RG')-A-(IN) (Ia),

wherein

(IN) is a photoinitiator base structure;

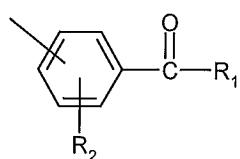
A is a spacer group or a single bond;

(RG) is hydrogen or at least one functional ethylenically unsaturated group; and

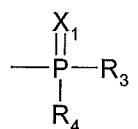
(RG') is a single bond or a divalent radical that contains at least one functional ethylenically unsaturated group, or is a trivalent radical.

5. (original) A process according to claim 4, wherein in the compound of formula I or Ia

(IN) is a photoinitiator base structure of formula (II) or (III)

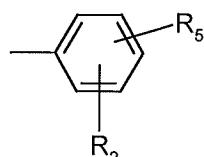


(II),



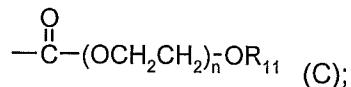
(III),

R₁ is a group (A), (B), (C) or (III)



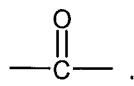
(A),

-CR₆R₇R₈ (B)



n is a number from 0 to 6;

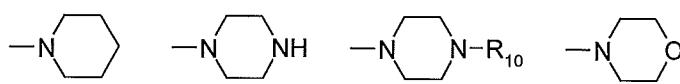
R₂ is hydrogen, C₁-C₁₂alkyl, halogen, the group (RG)-A- or, when R₁ is a group (A), two radicals



R₂ in the ortho-position to the carbonyl group may also together be -S- or -C=O-;

R₃ and **R₄** are each independently of the other C₁-C₆alkyl, C₁-C₆alkanoyl, phenyl or benzoyl, the radicals phenyl and benzoyl each being unsubstituted or substituted by halogen, C₁-C₆alkyl, C₁-C₆alkylthio or by C₁-C₆alkoxy;

R₅ is hydrogen, halogen, C₁-C₁₂alkyl or C₁-C₁₂alkoxy or the group (RG)-A-;



R₆ is OR₉ or N(R₉)₂ or is

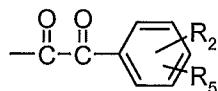
or SO₂R₉;

R₇ and **R₈** are each independently of the other hydrogen, C₁-C₁₂alkyl, C₂-C₁₂alkenyl, C₁-C₁₂alkoxy, phenyl or benzyl or R₇ and R₈ together are C₂-C₆alkylene;

R₉ is hydrogen, C₁-C₆alkyl or C₁-C₆alkanoyl;

R₁₀ is hydrogen, C₁-C₁₂alkyl or phenyl;

R_{11} is hydrogen, C_1 - C_4 alkyl or
 X_1 is oxygen or sulfur.



6. (previously presented) A process according to claim 5, wherein in the compound of formula I or Ia
 (RG) is $R_cR_bC=CR_a-$;

(RG') is $\begin{array}{c} CH_2 R_a \\ || \\ -C-C- \\ | \\ H_3C-Si- \end{array}$ or $\begin{array}{c} CH_2 R_a \\ || \\ -C-C- \\ | \\ R_b \end{array}$, and

R_a , R_b and R_c are each independently of the other hydrogen or C_1 - C_6 alkyl.

7. (previously presented) A process according to claim 1, wherein the photoinitiator(s) or mixtures thereof with monomers or oligomers are used in combination with one or more liquids in the form of solutions, suspensions and emulsions.

8. (previously presented) A process according to claim 1, wherein in process step d1) a photo-polymerisable composition, comprising at least one ethylenically unsaturated monomer or/and oligomer and at least one photoinitiator and/or coinitiator, is applied to the pretreated substrate and cured by means of UV/VIS radiation.

9. (previously presented) A process according to claim 1, wherein an inert gas or a mixture of inert gas with reactive gas is used as the plasma gas.

10. (original) A process according to claim 9, wherein air, H_2 , CO_2 , He, Ar, Kr, Xe, N_2 , O_2 or H_2O are used singly or in the form of a mixture.

11. (previously presented) A process according to claim 1, wherein the photoinitiator layer applied has a layer thickness of up to 500 nm.

12. (previously presented) A process according to claim 1, wherein process step b) is carried out immediately after process step a) or within 24 hours after process step a).

13. (previously presented) A process according to claim 1, wherein the concentration of photo-initiator or photoinitiators in process step b) is from 0.01 to 99.5 %.

14. (previously presented) A process according to claim 1, wherein process step c) is carried out immediately after process step b) or within 24 hours after process step b).

15. (previously presented) A process according to claim 1, wherein drying in process step b) is effected in ovens, with hot gases, heated rollers or IR or microwave radiators or by absorption.

16. (cancelled)

17. (original) A process according to claim 1, wherein portions of the photoinitiators, or mixtures thereof with monomers and/or oligomers, applied in process step b) that have not been crosslinked after irradiation in process step c) are removed by treatment with a solvent and/or water and/or mechanically.

18. (previously presented) A process according to claim 1, wherein after irradiation in process step d1) portions of the coating are removed by treatment with a solvent and/or water and/or mechanically.

19. (cancelled)

20. (withdrawn) A strongly adherent coating on an inorganic or organic metalized substrate obtained by a process according to claim 1.

21. (cancelled)

22. (previously presented) A process according to claim 1 wherein the inorganic or organic metalized substrate is a metalized thermoplastic, elastomeric, inherently crosslinked or crosslinked polymer, a ceramic material, a glass, a leather or a textile.